

IN THE CLAIMS

1 (Currently Amended). A method comprising:
forming a photoresist using a photoacid generator having a first ring including
iodine or sulfur and an aromatic ring and an anion selected from the group of ClO₄, SbF₆, and
perfluoroalkyl sulfonate.

2 (Original). The method of claim 1 including forming said first ring as a sigma-bonded ring.

3 (Original). The method of claim 1 including forming an aromatic ring as a phenyl group.

4 (Original). The method of claim 1 including forming a naphthyl ring structure.

5 (Original). The method of claim 1 including bonding said first ring directly to said aromatic ring to form a naphthyl ring.

Claims 6-10 (Canceled).

11 (Currently Amended). A photoresist comprising:
a photoacid generator including a first ring and an aromatic ring directly bonded to said first ring; and
said first ring including two atoms selected from the group including iodine and sulfur; and
an anion selected from the group of ClO₄, SbF₆, and perfluoroalkyl sulfonate.

12 (Original). The photoresist of claim 11 wherein said first ring is sigma-bonded.

13 (Original). The photoresist of claim 11 including two aromatic rings bonded to said first ring.

14 (Original). The photoresist of claim 13 wherein said aromatic rings are bonded on opposite sides of said first ring.

15 (Original). The photoresist of claim 6 wherein said aromatic ring is a phenyl group.

16 (Original). The photoresist of claim 11 wherein said aromatic ring has an alkyl, phenyl, or caged alkyl attached to said ring.

Claim 17 (Canceled).